## I. Amendments to the Specification

Please replace paragraph [0019] with the following amended paragraph:

[0019] As noted, it is a feature of the second p-type semiconductor layer 16 that it includes a graded doping concentration. The presence of dopants in the second p-type semiconductor layer 16 is controlled in order to optimize the performance of the photodiode. A first concentration 15 is located near the first p-type semiconductor 14, and a second concentration 17 is directly adjacent to the n-type semiconductor 18. Preferably, the first concentration 15 D is between 800 and 1,000 angstroms deep, i.e. the dimension parallel to the travel of the carriers.

Please replace paragraph [0020] with the following amended paragraph:

**[0020]** In the preferred embodiment, the first concentration 15 is greater than the second concentration 17. In particular, the first concentration 15 is located at a position  $x_0$  and defines a dopant concentration  $p_0$ . A preferred doping concentration gradient is governed by the following equation:

$$(1) p = p_o e^{\frac{-x}{D}}$$

over the depth D of the second p-type semiconductor layer 16 for all x and D greater than zero. A graph representative of Equation (1) is shown in Figure 4. A generic representation of the dopant concentration p is shown in Figure 4.

Please replace paragraph [0024] with the following amended paragraph:

[0024] Another aspect of the graded doping concentration of the second ptype semiconductor layer 16 is the creation of a pseudo-electric field. The electrons generated in the first concentration 15 region are subject to this pseudo-field shown below as

$$E = \begin{pmatrix} kT \\ q \end{pmatrix} \frac{dp}{dx} ,$$

$$(2) E = -\left(\frac{kT}{q}\right)\frac{dp}{dx}\frac{1}{p}.$$

where k is Boltzman's constant, T is the temperature, q is the charge of an electron, and the value  $\frac{dp}{dx}$  is the doping concentration gradient.